

What is claimed is:

1. A cleaning apparatus to clean alien substance from a substrate provided with a mask pattern prior to wet etching, the apparatus comprising:

an ultraviolet cleaner; and

a conveyer conveying the substrate to and from the ultraviolet cleaner.

2. The apparatus according to claim 1, wherein the conveyer includes:
a first conveyer conveying the substrate from a loader to the ultraviolet cleaner; and

a second conveyer conveying the substrate from the ultraviolet cleaner to a wet etching unit.

3. The apparatus according to claim 1, wherein the ultraviolet cleaner uses eximer ultraviolet light.

4. The apparatus according to claim 1, wherein the substrate includes at least one of a gate electrode, a source electrode, a drain electrode, a pixel electrode, and a protective layer.

5. The apparatus according to claim 1, wherein the substrate includes at least one of a black matrix and a common electrode.

6. A wet etching apparatus to clean alien substances from a substrate with a mask pattern prior to wet etching, the apparatus comprising:

an ultraviolet cleaner cleaning the alien substances from the substrate;

a conveyer conveying the substrate to and from the ultraviolet cleaner;

a loader loading the substrate to and from the ultraviolet cleaner; and

an etching unit etching the substrate that is free of the alien substances, the conveyer conveying the substrate from the ultraviolet cleaner into the etching unit.

7. The apparatus according to claim 6, wherein the conveyer includes:
a first conveyer conveying the substrate from the loader to the
ultraviolet cleaner; and
a second conveyer conveying the substrate from the ultraviolet cleaner
to the etching unit.

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8. The apparatus according to claim 6, wherein the ultraviolet cleaner
is installed at a predetermined area in the loader on the substrate having a
plurality of cassettes.

9. The apparatus according to claim 6, wherein the conveyer is
installed at a predetermined area between the ultraviolet cleaner and the
etching unit in the loader.

10. The apparatus according to claim 6, wherein the substrate
includes at least one of a gate electrode, a source electrode, a drain
electrode, a pixel electrode, and a protective layer.

11. The apparatus according to claim 6, wherein the substrate
includes at least one of a black matrix and a common electrode.

12. The apparatus according to claim 6, further comprising:
a tilt drain part flowing an etchant on the substrate;
a de-ionized rinse part eliminating the etchant on the substrate; and
a spin drier drying a de-ionized water.

13. A method to clean alien substances from a substrate with a
photoresist mask pattern, the method comprising:
forming the photoresist mask pattern on the substrate;
conveying the substrate to a clean device;
exposing the substrate to an ultraviolet light to remove the alien
substances; and

7 conveying the substrate from the cleaning device to an etching station.

1 14. The method according to claim 13, wherein the ultraviolet light
2 includes eximer ultraviolet light.

1 15. A method for wet etching comprising:
2 cleaning a substrate having an alien substances from an ultraviolet
3 cleaner;
4 conveying the substrate to and from the ultraviolet cleaner;
5 loading the substrate to a loader; and
6 etching the substrate in an etching unit.

1 16. The apparatus according to claim 15, wherein the substrate
2 includes at least one of a gate electrode, a source electrode, a drain
3 electrode, a pixel electrode, and a protective layer.

1 17. The apparatus according to claim 15, wherein the substrate
2 includes at least one of a black matrix and a common electrode.

5/18/2002 18. The apparatus according to claim 15, further comprising:
2 flowing an etchant on the substrate in a tilt drain part;
3 eliminating the etchant on the substrate in a de-ionized rinse part
4 having a de-ionized water; and
5 drying the de-ionized water in a spin drier.